



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. .... 09/388,826  
Filing Date ..... September 1, 1999  
Inventor ..... Weimin (Michael) Li et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2813  
Examiner ..... E. Kielin  
Attorney's Docket No. .... MI22-1208  
Title: Low k Interlevel Dielectric Layer Fabrication Methods

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

References -See Attached Form PTO-1449

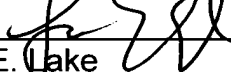
In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the references which are listed on the attached Form PTO-1449, copies of which are attached.

No admission is made regarding whether all the submitted references are prior art.

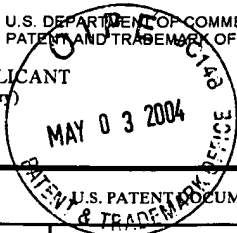
Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: 03 May 2004

By:   
James E. Lake  
Reg. No. 44,854

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1208		SERIAL NO. 09/388,826	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li, et al.			
				FILING DATE September 1, 1999		GROUP 2813	



*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,985,519	11/1999	Kakamu et al.		
	AB	5,747,388	05/1998	Kusters et al		
	AC	5,639,687	06/1997	Roman et al		
	AD	5,498,555	03/1996	Lin		
	AE	6,153,504	11/2000	Shields et al		
	AF	4,971,655	11/1990	Stefano et al		
	AG	6,498,084	12/2002	Bergemont		
	AH	5,036,383	07/1991	Mori		
	AI					
	AJ					
	AK					
	AL					

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
AM	6232113	08/1994	Japan				
AN	8051058	02/1996	Japan				
AO	63316476	12/1988	Japan				
AP	8078322	03/1996	Japan				
AQ	10-163083	06/1998	Japan				
AR	08-045926A	02/1996	Japan				

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
AS			
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li, et al.	
					FILING DATE September 1, 1999	GROUP 2813
U.S. PATENT DOCUMENTS						
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,503,818 B1	01/2003	Jang		
	AB	6,486,061 B1	11/2002	Xia et al.		
	AC	6,486,057 B1	11/2002	Yeh et al.		
	AD	6,465,372 B1	10/2002	Xia et al.		
	AE	6,444,593 B1	09/2002	Ngo et al.		
	AF	6,436,808 B1	08/2002	Ngo et al.		
	AG	6,435,943 B1	08/2002	Chang et al.		
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	AI	6,284,677 B1	09/2001	Hsiao et al.		
	AJ	6,030,901	02/2000	Hopper et al.		
	AK	6,133,618	10/2000	Steiner		
	AL	5,994,217	11/1999	Ng		
FOREIGN PATENT DOCUMENTS						
	Document Number	Date	Country	Class	Subclass	Translation Yes      No
	AM	8046186	02/1996	Japan		
	AN	8046186	2/1996	Japan		X
	AO	7201716	08/1995	Japan		
	AP	7201716	08/1995	Japan		X
	AQ	8046188	02/1996	Japan		
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)						
	AR	Wolf, S., Silicon Process., V.1 407-413.				
	AS	Wolf, S., Silicon Process., Vol. 2 48-49 and 435.				
	AT	Wolf, S., Silicon Processing for the VLSI Era, Vol. 3, page 635.				
EXAMINER				DATE CONSIDERED		
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